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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/674,017	09/30/2003	Myoung-Kee Baek	8734.240.00 US	2379
30827 7590 06/02/2009 MCKENNA LONG & ALDRIDGE LLP 1900 K STREET, NW WASHINGTON, DC 20006				
EXAMINER TALBOT, BRIAN K				
ART UNIT		PAPER NUMBER		
1792				
MAIL DATE		DELIVERY MODE		
06/02/2009		PAPER		

**Please find below and/or attached an Office communication concerning this application or proceeding.**

The time period for reply, if any, is set in the attached communication.

# Office Action Summary

**Application No.**

10/674,017

**Applicant(s)**

BAEK ET AL.

**Examiner**

Brian K. Talbot

**Art Unit**

1792

-- The MAILING DATE of this communication appears on the cover sheet with the correspondence address --  
**Period for Reply**

A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) OR THIRTY (30) DAYS, WHICHEVER IS LONGER, FROM THE MAILING DATE OF THIS COMMUNICATION.

- Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication.
- If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication.
- Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).

**Status**

- 1) ☒ Responsive to communication(s) filed on 27 March 2009.  
2a) ☐ This action is **FINAL**. 2b) ☒ This action is non-final.  
3) ☐ Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under *Ex parte Quayle*, 1935 C.D. 11, 453 O.G. 213.

**Disposition of Claims**

- 4) ☒ Claim(s) 1-3, 5-10 and 12 is/are pending in the application.  
4a) Of the above claim(s) \_\_\_\_\_ is/are withdrawn from consideration.  
5) ☐ Claim(s) \_\_\_\_\_ is/are allowed.  
6) ☒ Claim(s) 1-3, 5-10 and 12 is/are rejected.  
7) ☐ Claim(s) \_\_\_\_\_ is/are objected to.  
8) ☐ Claim(s) \_\_\_\_\_ are subject to restriction and/or election requirement.

**Application Papers**

- 9) ☐ The specification is objected to by the Examiner.  
10) ☐ The drawing(s) filed on \_\_\_\_\_ is/are: a) ☐ accepted or b) ☐ objected to by the Examiner.  
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).  
Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).  
11) ☐ The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.

**Priority under 35 U.S.C. § 119**

- 12) ☐ Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).  
a) ☐ All b) ☐ Some \* c) ☐ None of:  
1. ☐ Certified copies of the priority documents have been received.  
2. ☐ Certified copies of the priority documents have been received in Application No. \_\_\_\_\_.  
3. ☐ Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).

\* See the attached detailed Office action for a list of the certified copies not received.

**Attachment(s)**

- 1) ☒ Notice of References Cited (PTO-892)  
2) ☐ Notice of Draftsperson's Patent Drawing Review (PTO-948)  
3) ☐ Information Disclosure Statement(s) (PTO-8508)  
Paper No(s)/Mail Date \_\_\_\_\_  
4) ☐ Interview Summary (PTO-413)  
Paper No(s)/Mail Date \_\_\_\_\_  
5) ☐ Notice of Informal Patent Application  
6) ☐ Other: \_\_\_\_\_

***Continued Examination Under 37 CFR 1.114***

1. A request for continued examination under 37 CFR 1.114, including the fee set forth in 37 CFR 1.17(c), was filed in this application after final rejection. Since this application is eligible for continued examination under 37 CFR 1.114, and the fee set forth in 37 CFR 1.17(c) has been timely paid, the finality of the previous Office action has been withdrawn pursuant to 37 CFR 1.114. Applicant's submission filed on 3/27/09 has been entered.
2. Claims 4,11 and 13 have been canceled. Claims 1-3,5-10 and 12 remain in the application.
3. The text of those sections of Title 35, U.S. Code not included in this action can be found in a prior Office action.
4. This application currently names joint inventors. In considering patentability of the claims under 35 U.S.C. 103(a), the examiner presumes that the subject matter of the various claims was commonly owned at the time any inventions covered therein were made absent any evidence to the contrary. Applicant is advised of the obligation under 37 CFR 1.56 to point out the inventor and invention dates of each claim that was not commonly owned at the time a later invention was made in order for the examiner to consider the applicability of 35 U.S.C. 103(c) and potential 35 U.S.C. 102(e), (f) or (g) prior art under 35 U.S.C. 103(a).

***Claim Rejections - 35 USC § 112***

5. The following is a quotation of the second paragraph of 35 U.S.C. 112:

The specification shall conclude with one or more claims particularly pointing out and distinctly claiming the subject matter which the applicant regards as his invention.

Claim 1 is rejected under 35 U.S.C. 112, second paragraph, as being indefinite for failing to particularly point out and distinctly claim the subject matter which applicant regards as the invention.

The step of 'separating the master from the substrate to leave the resist on the substrate' is confusing as the master is already separated from the substrate. It appears that this should recite "separating the resist from the master to leave the resist on the substrate". Clarification is requested.

***Claim Rejections - 35 USC § 103***

6. Claims 1-3,6-10 and 12 are rejected under 35 U.S.C. 103(a) as being unpatentable over Hattori et al. (5,403,616) in combination with JP 08-031,830 (a) alone or (b) further in combination with Yamuni et al. (6,730,358).

Hattori et al. (5,403,616) teaches a method of forming patterned transparent conductive film. The patterning process comprises forming a masking pattern (2) on a substrate (10), applying the coating layer (3), heating the coating layer and the mask to set the coating layer and remove the mask to form the patterned layer (abstract, Figs. 1a-1e, 2a-2e and col. 2, line 60 – col.

3, line 65). Hattori et al. (5,403,616) teaches the process utilized for LCD devices (col. 1, lines 9-25). The glass substrate can have a coating of silica thereon prior to the application of the patterned coating layer (examples). The coating layer can be applied by spin coating, dip coating or roll coating (col. 4, lines 41-64). Hattori et al. (5,403,616) teaches physically removing the masking pattern by ultrasonic cleaning or gas jet of air (col. 4, lines 28-40).

Hattori et al. (5,403,616) fails to teach a master being separately formed and separable from the substrate. In addition, the use of a doctor blade to planarize the resist coating for claims 10-13.

JP 08-031,830 teaches a solder bump forming process whereby a mask is set with a distance above the substrate and solder is filled in the mask. The solder can be placed on the substrate by die punching (Figs. 1A-1D) or by being close enough to the substrate (Figs. 4A-4D).

Therefore, it would have been obvious for one skilled in the art at the time the invention was made to have modified Hattori et al. (5,403,616) process by substituting a “displaced mask” as evidenced by JP 08-031,830 for the mask of Hattori et al. (5,403,616) with the expectation of achieving similar success.

(a) Hattori et al. (5,403,616) in combination with JP 08-031,830 fail to teach a distance between the master and substrate being a few micrometers.

While this may be the case, it is the Examiner’s position that the distance between the mask and the substrate would be a matter of design choice of one practicing in the art depending upon the desired end product. It is would be within the skill of one practicing in the art to separate the mask from the substrate at a “distance” equal to or slightly greater than the “height” of the paste being applied to assure placement upon the substrate. These parameters are “result

effective variables" which are deemed as an unpatentable distinction over the art absent a showing of unexpected results.

(b) Hattori et al. (5,403,616) in combination with JP 08-031,830 fail to teach a distance between the master and substrate being a few micrometers.

Yamuni et al. (6,730,358) teaches a method for depositing conductive paste using stencil whereby a mask having a thickness of 0.001-0.008 microns being displaced from the substrate and the pins are about greater than 40% of the length of the aperture to from the coating (col. 4, lines 32-40 and col. 6, lines 50-63). With this in mind the distance between the mask and the substrate must be equal to or less then the thickness of the mask and therefore meets the claimed invention. This is the same argument presented by applicant in the response filed 1/28/09, i.e. there is a correspondence between thickness of mask and distance between mask and substrate.

Therefore it would have been obvious for one skilled in the art at the time the invention was made to have modified Hattori et al. (5,403,616) in combination with JP 08-031,830 process to have a distance between the master and substrate being a few micrometers as evidenced by Yamuni et al. (6,730,358) with the expectation of achieving similar success.

Claim 5 is rejected under 35 U.S.C. 103(a) as being unpatentable over Hattori et al. (5,403,616) in combination with JP 08-031,830 (a) alone or (b) further in combination with Yamuni et al. (6,730,358) either (a) or (b) further in combination with Applicant's admitted state of the art (specification pg. 2-5 and Figs. 1-2).

Hattori et al. (5,403,616) in combination with JP 08-031,830 (a) alone or (b) further in combination with Yamuni et al. (6,730,358) fail to teach and etching layer being metal.

Applicant's admitted state of the art (specification pg. 2-5 and Figs. 1-2) teaches that gate electrodes, drain electrodes and pixel electrodes are formed on a glass substrate for LCD manufacture.

Therefore it would have been obvious for one skilled in the art at the time the invention was made to have modified over Hattori et al. (5,403,616) in combination with JP 08-031,830 (a) alone or (b) further in combination with Yamuni et al. (6,730,358) process by including a metal electrode layer to be etched as evidenced by Applicant's admitted state of the art (specification pg. 2-5 and Figs. 1-2) with the expectation of achieving similar success, i.e. a patterned layer.

### ***Response to Amendment***

7. Applicant's arguments with respect to claims 1-3,5-10 and 12 have been considered but are moot in view of the new ground(s) of rejection.

Applicant argued that the prior art fails to teach a master separated from the substrate during the filling of the master.

Yamuni et al. (6,730,358) teaches this limitation as detailed above. Furthermore, JP 08-031,830 teaches a distance of a few hundred microns between the mask and substrate and this would be deemed as a "result effective variable" optimized by one skilled in the art dependent upon the desired end product and therefore unpatentable absent a showing of unexpected results.

8. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Brian K. Talbot whose telephone number is (571) 272-1428. The examiner can normally be reached on Monday-Friday 8AM-4PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Timothy H. Meeks can be reached on (571) 272-1423. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see <http://pair-direct.uspto.gov>. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

/Brian K Talbot/  
Primary Examiner, Art Unit 1792

BKT